## **Supplementary Information**

## Demonstration of surface transport in a hybrid Bi<sub>2</sub>Se<sub>3</sub>/Bi<sub>2</sub>Te<sub>3</sub> heterostructure

Yanfei Zhao<sup>1, #</sup>, Cui-Zu Chang<sup>2, 3#</sup>, Ying Jiang<sup>4</sup>, Ashley DaSilva<sup>5</sup>, Yi Sun<sup>1</sup>, Huichao Wang<sup>1</sup>, Ying Xing<sup>1</sup>, Yong Wang<sup>4</sup>, Ke He<sup>2,\*</sup>, Xucun Ma<sup>2</sup>, Qi-Kun Xue<sup>2, 3</sup>, and Jian Wang<sup>1, \*</sup>

<sup>1</sup>International Center for Quantum Materials, School of Physics, Peking University, Beijing 100871, People's Republic of China

<sup>2</sup>Institute of Physics, Chinese Academy of Sciences, Beijing 100190, China

<sup>3</sup>State Key Lab of Low-Dimensional Quantum Physics, Department of Physics, Tsinghua University, Beijing 100084, China

<sup>4</sup>Center of Electron Microscopy, State Key Laboratory of Silicon Materials, Department of Materials Science and Engineering, Zhejiang University, Hangzhou, 310027, China

<sup>5</sup>Department of Physics, University of Texas at Austin, Austin, Texas 78712-1081, USA

<sup>#</sup>Authors equally contributed to this work.

\*Correspondence and requests for materials should be addressed to J. W.

(jianwangphysics@pku.edu.cn) and K. H. (kehe@iphy.ac.cn).

### **Supplementary Information**

# Hall Measurements of 20 QLs $Bi_2Se_3$ , 20 QLs $Bi_2Te_3$ and 1 QL $Bi_2Se_3$ / 19 QLs $Bi_2Te_3$



Fig. S1: Hall resistance of the 20 QLs  $Bi_2Se_3$  film (a), 20 QLs  $Bi_2Te_3$  film (c) and 1 QL  $Bi_2Se_3$  / 19 QLs  $Bi_2Te_3$  thin film (e) at 2 K. Temperature dependence of mobility for three samples, (b) for 20 QLs  $Bi_2Se_3$ , (d) for 20 QLs  $Bi_2Te_3$  and (f) for 1 QL  $Bi_2Se_3$  / 19 QLs  $Bi_2Te_3$  thin films.

We determine the carrier density in the three samples using the Hall effect, as shown in Fig. S1. The carriers are electrons in all three samples. From the approximately linear behavior of  $R_{xy}$  at low magnetic field, we estimate a carrier density of  $3.53 \times 10^{19}$  cm<sup>-3</sup> and mobility of 650 cm<sup>2</sup>/vs for the 20 QLs Bi<sub>2</sub>Se<sub>3</sub> film at 2

K. For the 20QLs  $Bi_2Te_3$  film, carrier density is  $4.17 \times 10^{19} cm^{-3}$  and mobility is  $912 cm^2/vs$ . The carrier density of the 1 QL  $Bi_2Se_3$  / 19 QLs  $Bi_2Te_3$  film is  $7.9 \times 10^{19} cm^{-3}$  and the mobility is  $134 cm^2/vs$ .



Complete transport data of Fig. 3f

Fig. S2: The complete transport data on the 1 QL Bi<sub>2</sub>Se<sub>3</sub> / 19 QLs Bi<sub>2</sub>Te<sub>3</sub> film as a function of temperature at different magnetic field, indicates that a logarithmic increase with decreasing *T*. In the upper inset, the slope defined as  $\kappa = (\pi h/e^2) d\sigma_{xx}/d\ln T$  is shown as a function of magnetic field. The  $\kappa$  increases with increasing the magnetic field and becomes a constant when the magnetic field ranges from 10 kOe to 150 kOe.



The Linear MR of the 1 QL Bi<sub>2</sub>Se<sub>3</sub> / 19 QLs Bi<sub>2</sub>Te<sub>3</sub> film at different tilt angle

Fig. S3: Normalized MR vs magnetic field of the 1 QL  $Bi_2Se_3$  / 19 QLs  $Bi_2Te_3$  film at 2 K at different tilt angle between sample surface and the magnetic field.

In perpendicular magnetic field ( $\theta$ =0deg), the sample exhibited a linear, non-saturated behavior across a wide range of magnetic field from 10 kOe to 150 kOe. The behavior gradually decreased when the sample was tilted away from the perpendicular angle and eventually became nonlinear in the parallel magnetic field ( $\theta$ =90deg). It indicates that the linear MR is a 2D magneto-transport behavior.

The fitting combined weak antilocalization with e-e interaction theory of 1 QL  $Bi_2Se_3$  / 19 QLs  $Bi_2Te_3$  film in low field at T=4K



Fig. S4: Solid lines are the results of a combined WAL and EEI theory<sup>S1</sup>. Considering the g-factor of 1 QL  $Bi_2Se_3$  / 19 QLs  $Bi_2Te_3$  film is not so sure, we fixed g-factor to be 30 and 20. The fitting curves are plotted by blue and orange respectively.

The combined model <sup>S1</sup>:  $\Delta\sigma(T,H_{\perp}) = \Delta\sigma_{\scriptscriptstyle W\!AL}(T,H_{\perp}) + \Delta\sigma_{\scriptscriptstyle E\!E\!I}(T,H_{\perp})$ 

$$\Delta \sigma_{WAL} = -\frac{\alpha e^2}{2\pi^2 \hbar} \left[ \ln \left( \frac{\hbar}{4Bel_{\phi}^2} \right) - \psi \left( \frac{1}{2} + \frac{\hbar}{4Bel_{\phi}^2} \right) \right] \text{ and } \Delta \sigma_{EEI} = -\frac{e^2}{4\pi^2 \hbar} \tilde{F}_{\sigma} g_2(T, H)$$
  
Where  $g_2(T, H) = \int_0^\infty d\Omega \ln \left| 1 - \left( \frac{g\mu_B H / k_B T}{\Omega} \right)^2 \right| \frac{d^2}{d\Omega^2} \frac{\Omega}{e^{\Omega} - 1}$ 

 $\alpha$  ,  $\;\tilde{F}_{\sigma}\;$  and \;  $l_{\boldsymbol{\phi}}\;$  are taken as fitting parameters.

g-factor	α	$l_{\phi}$	$ ilde{F}_{\sigma}$
30	-0.32	194nm	0.6
20	-0.25	193nm	0.93

The fitting parameters are as follows:

#### Reference

S1. Wang, J. et al. Evidence for electron-electron interaction in topological insulator thin films. *Phys. Rev. B.* **83**, 245438 (2011).